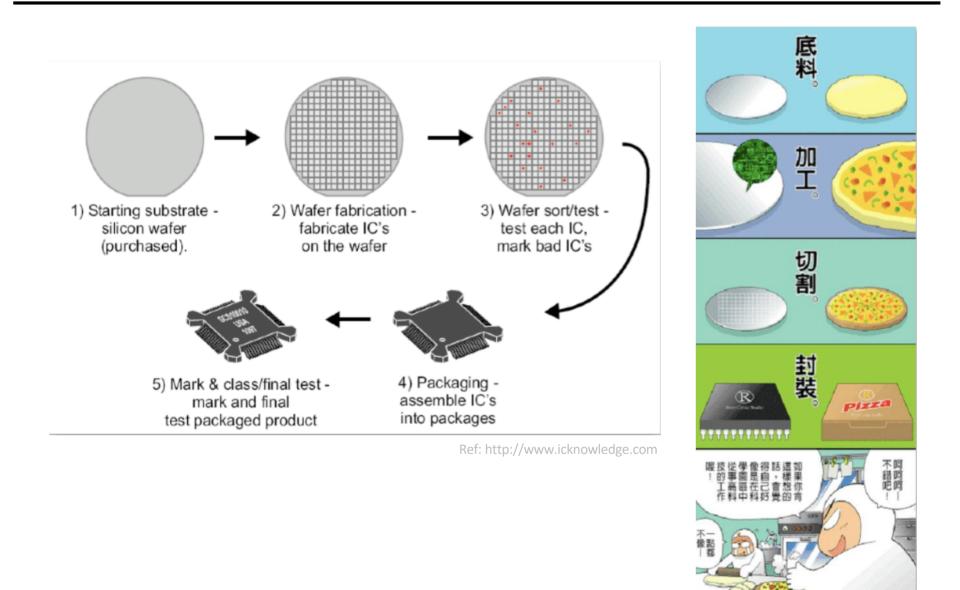
# Outline

- Brief IC history
- CMOS fabrication
- Design partitioning
- Simple example of custom design

#### **Measure of IC**

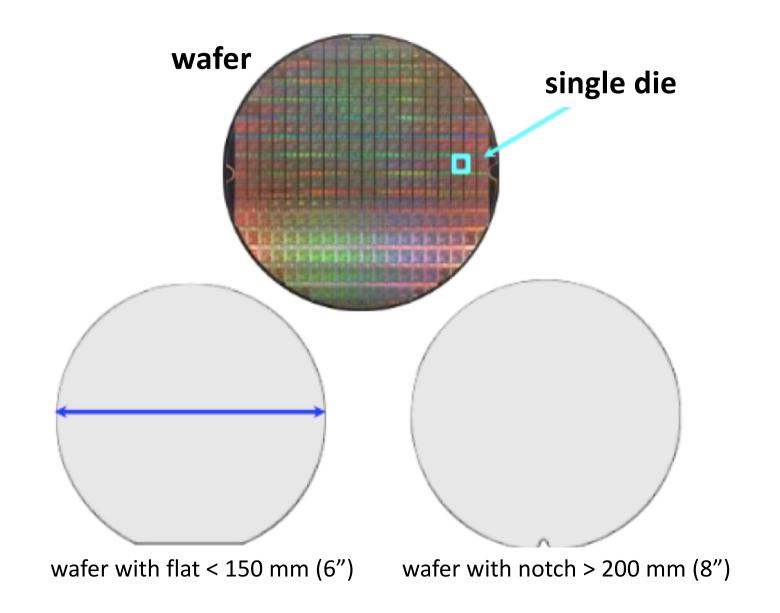
- Gate equivalent, two-input NAND gate (of 4 transistors)
- Terms
  - SSI (small-scale IC: 60's): 10 gates
  - MSI (medium-scale IC: early 70's): 1000 gates
  - LSI (large-scale IC: late 70's): 10000 gates
  - VLSI (very-large-scale IC: early 80's): > LSI
  - ULSI (ultra-large-scale IC): millions gates

#### **Wafer Fabrication Process**

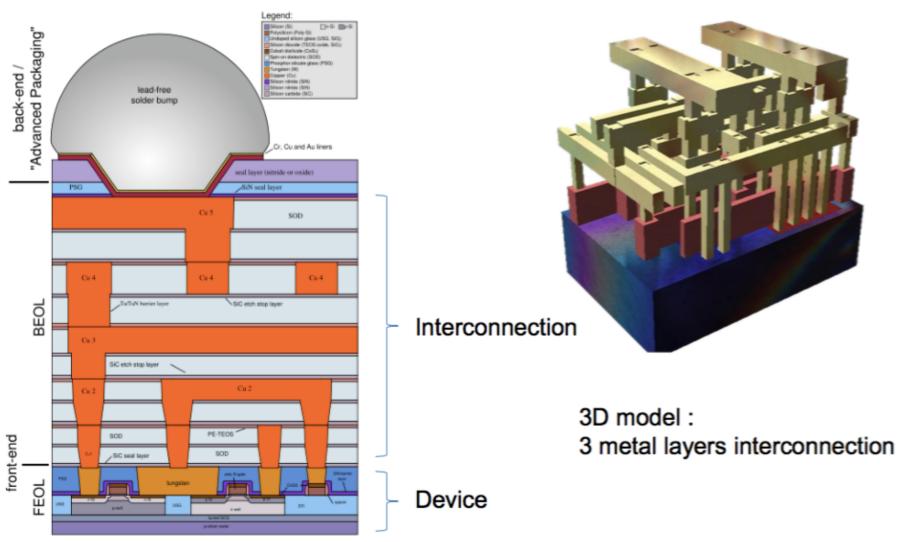


www.river.com.tw

#### Wafer and Die

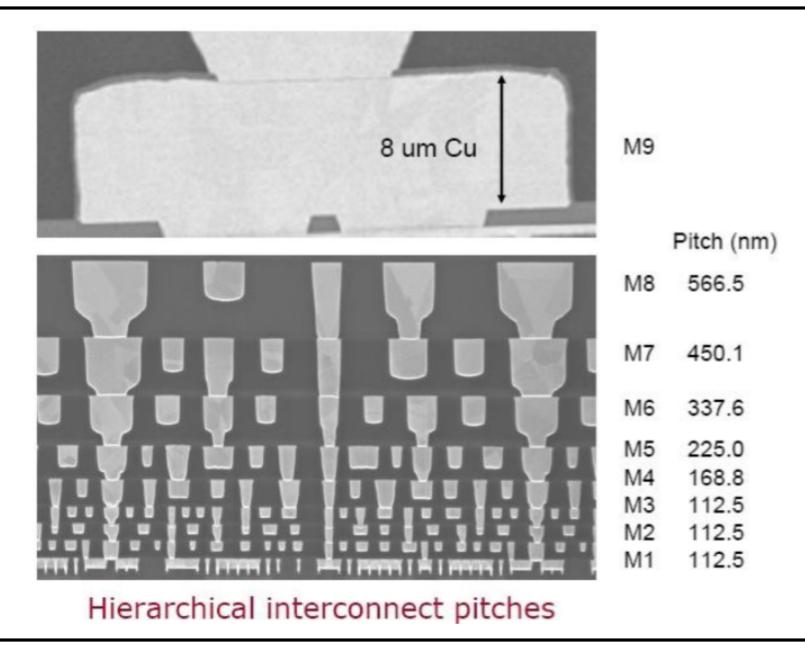


#### **Integrated Circuit Cross-Section**

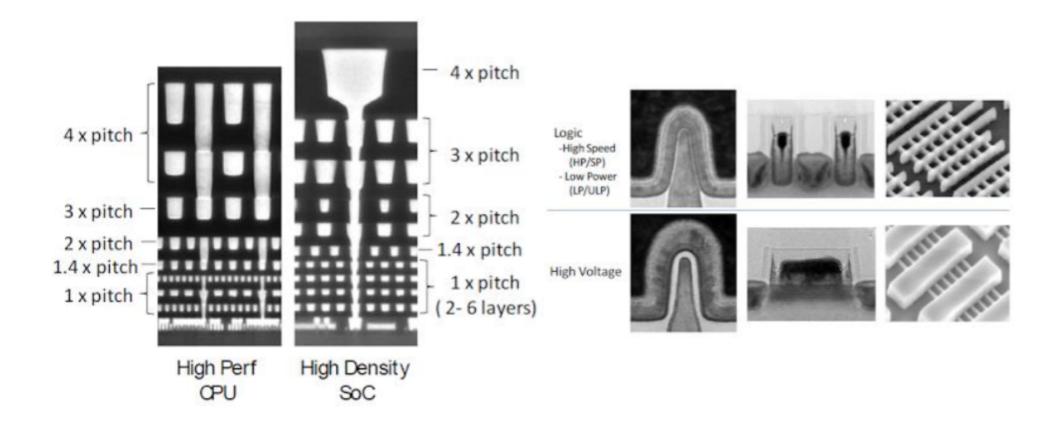


Ref: http://en.wikipedia.org/wiki/integrated\_circuit

#### **32 nm Interconnect**



#### **Intel 22 nm Trigate Process**



# **Cost of Integrated Circuits**

- Non-recurrent engineering (NRE) costs
  - One-time cost factors
  - Design effort, design time, mask generation
- Recurrent costs
  - Proportional to chip area and volume
  - Silicon processing, packaging, testing

#### **Fabrication Cost**

Year	1999	2002	2005	2008	2011	2014
Feature size (nm)	180	130	100	70	50	35
Chip size (mm <sup>2</sup> )	170	214	235	269	308	354
Logic trans/Chip (M)	15	60	235	925	3,650	14,400

- Cost of building factories increases 2X every 3 years
  - By 2010 a fab (12") may cost \$3 billion
  - By 2014 (18") it may cost 8~10 billion
- Mask costs are growing rapidly adding more to upfront NRE for new designs
  - Next-generation lithography methods require expensive complex masks (optical proximity correction (OPC) and phase shift (PSM)) to have low error tolerances
  - Multiple masks that require longer write times increase mask production costs

### Mask Cost

	•		32/28nm node	22/20nm node
Technology	Mask Cost	Fab Costs	\$3B	\$4B-7B
250nm	\$100K *			
180nm	\$350K *	Process R&D	\$1.2B	\$2.1B-3B
130nm	\$750K *	Design Costs	\$50M-90M	\$120M-500M
90nm	\$1.5M *	Mask Costs	\$2M-3M	\$5M-8M
65nm	\$3M **			Source: IBS May 2011
35nm	\$6M **	EDA Costs	\$400M-500M	\$800M-1.2B

- Double Jeopardy!
  - 1) The potential for bugs goes up
  - 2) The cost of re-spinning the chip goes up

#### → You cannot afford hardware bugs!!

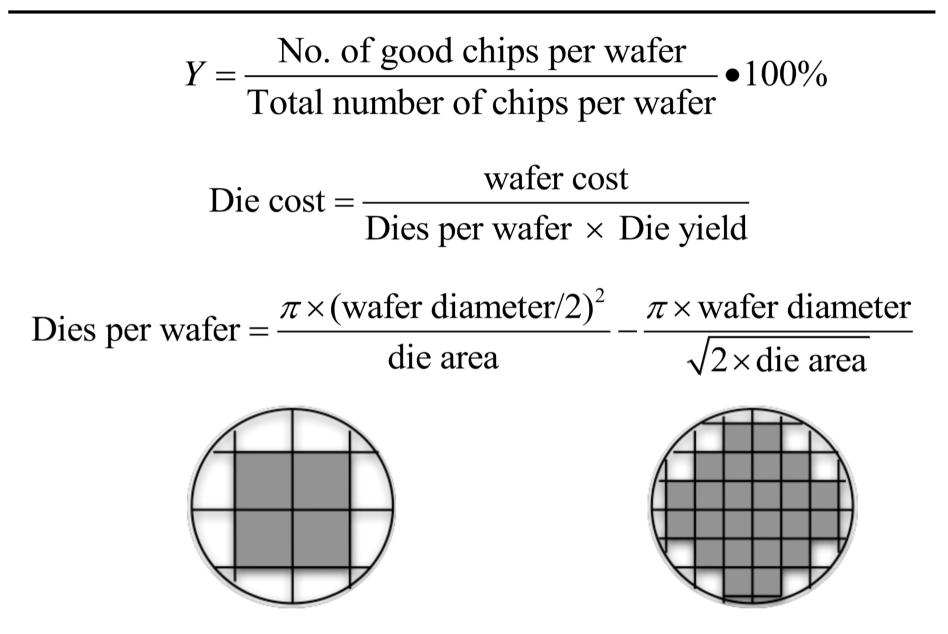
Charles Moore, "Managing the Transition from Complexity to Elegance", ISCAS 2003

## **Design Productivity Crisis**

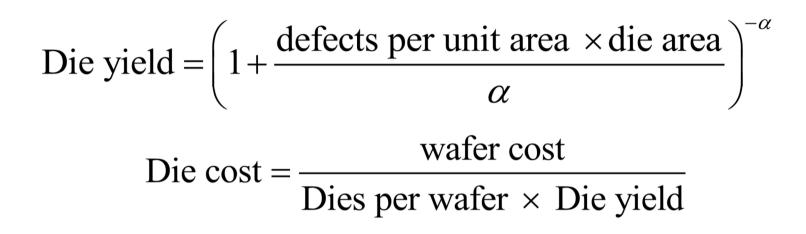
Year	Tech. (nm)	Complexity	Frequency	3 Yr. Design Staff Size	Staff Costs
1997	350	13 M Tr.	400 MHz	210	\$90 M
1998	250	20 M Tr.	500 MHz	270	\$120 M
1999	180	32 M Tr.	600 MHz	360	\$160 M
2002	130	130 M Tr.	800 MHz	800	\$360 M

- 1996: 100 people in P6 team
- 2007: 1600 people in P10 team
- Question: ?? People in P38 team?
- Improve productivity through design animation

#### Yield



#### Defects



*if*  $\alpha = 3$ , die cost = f(die area)<sup>4</sup>



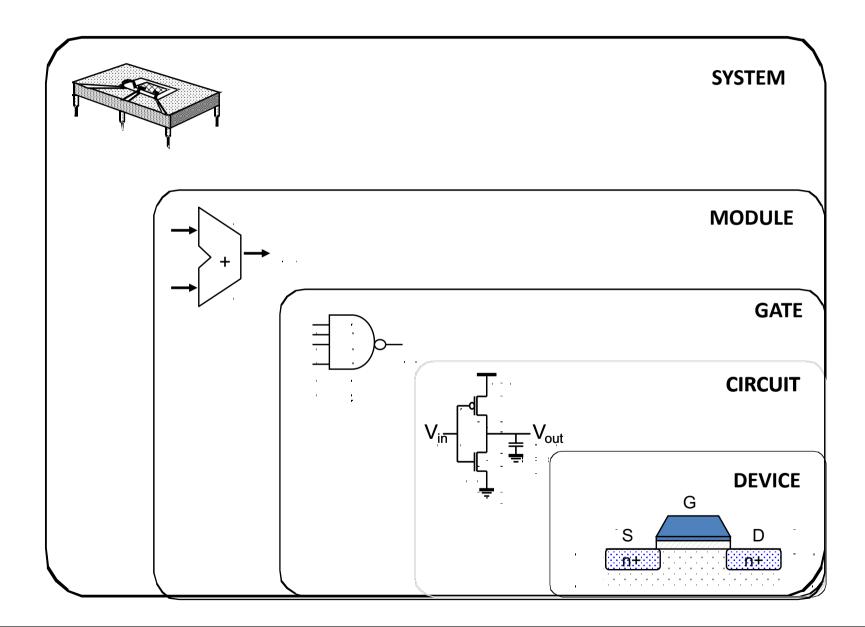
### **Yield Example**

- Wafer size of 12", die size of 2.5 cm<sup>2</sup>, 1 defects/cm<sup>2</sup>,
  α = 3 (measure of manufacturing process complexity)
- 252 dies/wafer
  - Wafers are round & dies are square
- Die yield of 16%
- 252 x 16% = only 40 dies/wafer die yield!
- Die cost is strong function of die area
  - Proportional to the third or fourth power of the die area

# Outline

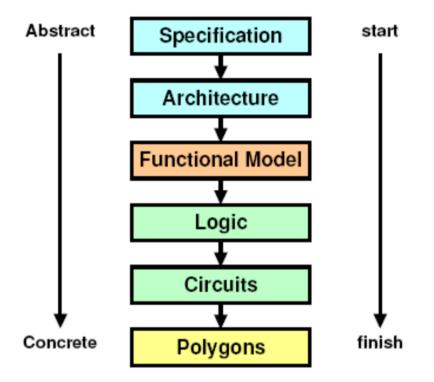
- Brief IC history
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#### **Design Abstraction Levels**



#### **From Specifications to Hardware**

- Target: spec in → hardware out
- Profitable hardware
  - Performance, yield and cost
- Design flow
  - You need good methodology
    & tools to help
- Validation
  - Functional & power
  - Testing efficiency & coverage



### **Design Metrics**

- How to evaluate performance of a circuit?
  - Speed (delay, operating frequency)
  - Design complexity
  - Power dissipation
  - Energy to perform a function
  - Cost (NRE and recurring)
  - Reliability (noise margin and immunity)
  - Scalability
  - Time-to-market

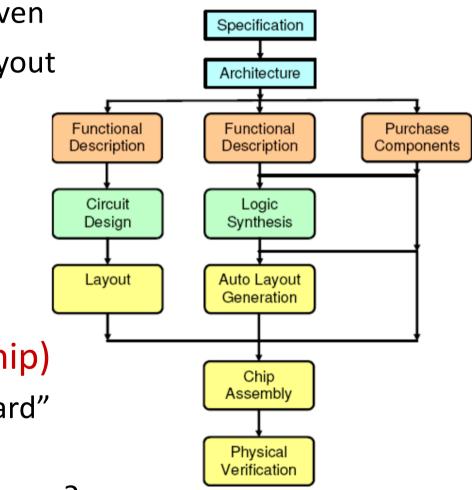
# **Design Types**

- FPGA design (EE2230 Logic Design Lab)
  - Configurable logic blocks, interconnects and I/Os
- Gate array design
  - Two step manufacturing, shorter silicon finished time
- Cell-based design (EE4292 IC Design Lab)
  - "Describe-and-synthesize" paradigm
- Full-custom design (EE5250, EE4292 IC Design Lab)
  - "Capture-and-simulate" paradigm
- SoC design
  - Platform-based design (reuse)

# **Design Flow**

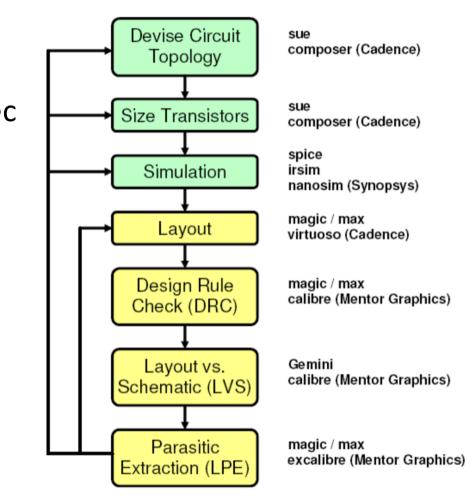
#### • Left: Full Custom

- Performance and area driven
- Hand-made design and layout
- Center: ASIC (Application-Specific Integrated Circuit)
  - Cell library +
    customized interconnect
- Right: SoC (System-on-Chip)
  - Silicon "printed circuit board"
  - Higher integration level
    - = better cost and performance?



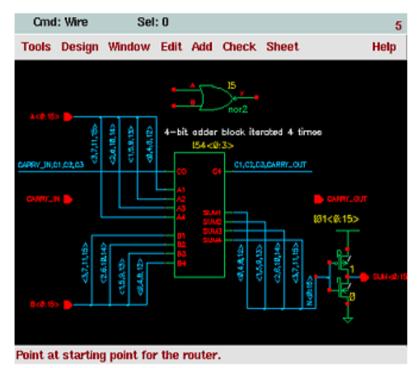
# **Full-Custom Design Flow**

- Analog or mixed-mode design flow
  - Customized function, technology, shape and spec
- Pros
  - Optimized area and performance
- Cons
  - Time and human source
  - May not re-usable



### **Schematic and Simulation**

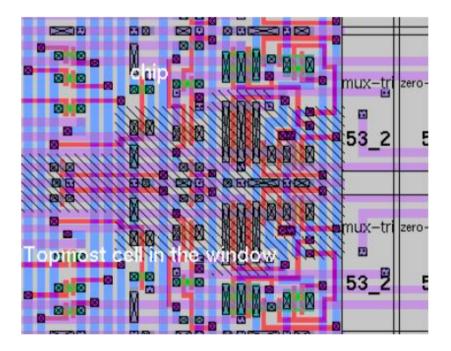
- GUI schematic entry
  - MOS (Transistor)  $\rightarrow$  Gate
    - $\rightarrow$  Sub-circuit (Symbol)
    - → Full-chip (System)
  - Easy for hieratical design and debugging
- Netlist Generation
  - For SPICE simulation and LVS
  - DO NOT use text editor
    to create your netlist



Cadence Virtuoso Schematic Composer

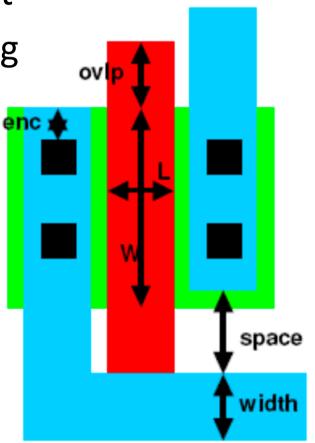
# Layout

- Polygons entry
  - Transformed from device netlist to polygons
  - Keep device's 3D cross section view in mind when drawing 2D polygons
  - Try to match schematic's hierarchy
  - Need to consider matching, routing parasitics, and coupling coupling, etc.
- Gds file Generation
  - For MASK layer definition



# **Design Rule Check (DRC)**

- Design rules are defined by foundry for semiconductor manufacturing process
- Study DRC rules before start Layout
- Need to know the physical meaning
- Design rule violation is
  NOT ALLOWED unless you are doing some experiments



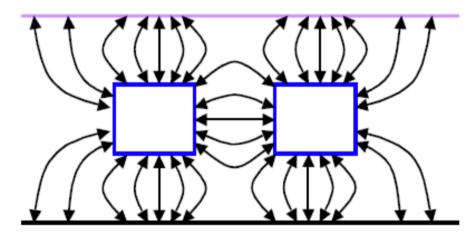
### Layout vs. Schematic (LVS)

- Make sure the layout matches your schematics
  - Debugging requires good methodology and experience



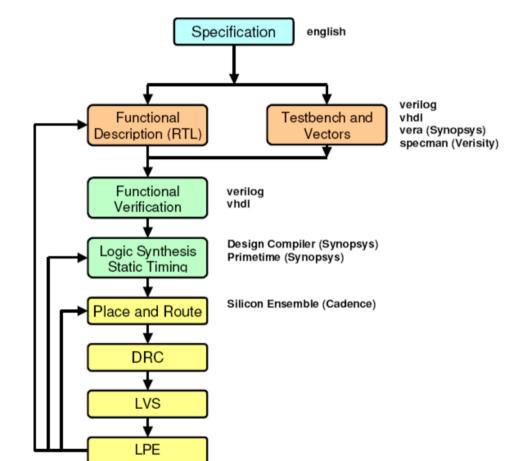
# Layout Parasitic Extraction (LPE)

- Extract parasitic resistance and capacitance
- Parasitic: the effect you didn't consider at the the first design phase (pre-layout simulation)
- Use LPE netlist to do post-layout simulation and check the close-to-real performance
- Post-simulation is NECESSARY and IMPORTANT



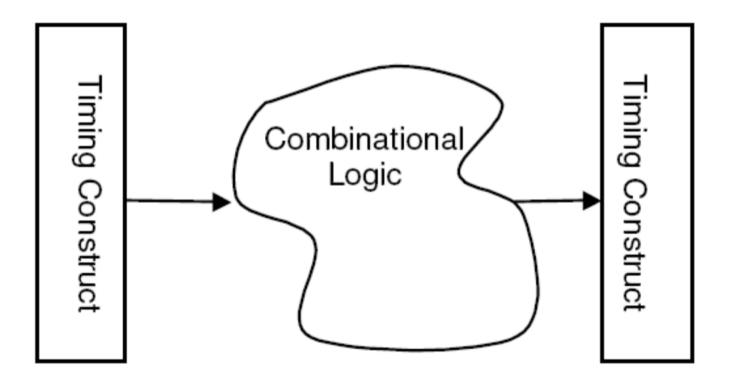
## **ASIC Design Flow**

- Digital design dlow
- Design based on standard cell library
- Pros
  - Reliable and expectable chip performance
- Cons
  - Not area and performance optimized
  - Need IP cost



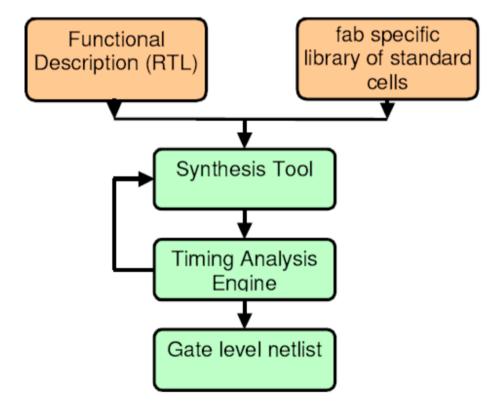
### **Register Transfer Level**

- Separate sections of combinational logic by timing statements
- Define behavior of each part on clock boundary (edge)



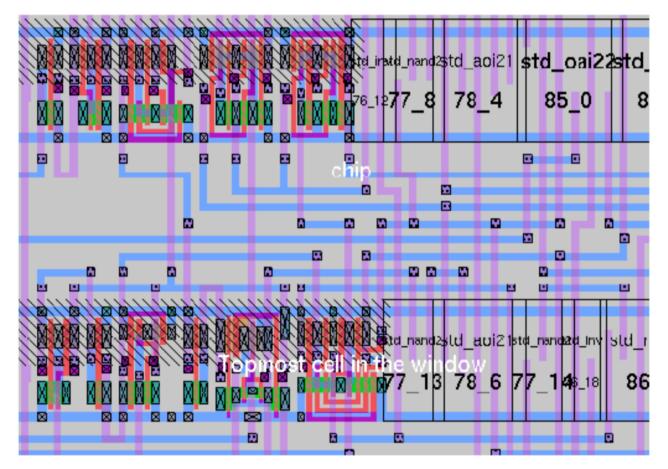
# **Logic Synthesis**

- Synthesize combinational functions into standard cells (gates) from fab-specific library
- Choose IP based on timing concern (rise/falling, delay)



## Auto Place and Route (APR)

- Cell placement and routing generated by CAD
- Area/delay minimization and loading optimization



"Introduction to VLSI Design 2008", Prof. Subhasish Mitra @ Stanford

# **System-on-Chip Design Flow**

- Architecture plan, sub-block spec and interface definition
- Buy Intellectual Property (IP) from various vendors

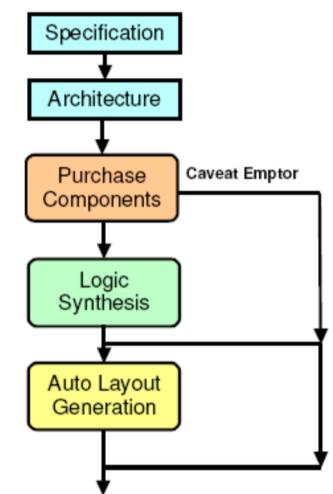
• Soft IP:

RTL of gate level description

- Synthesize and APR for your process
- **Ex** USB controller
- Hard IP:

Polygon level description

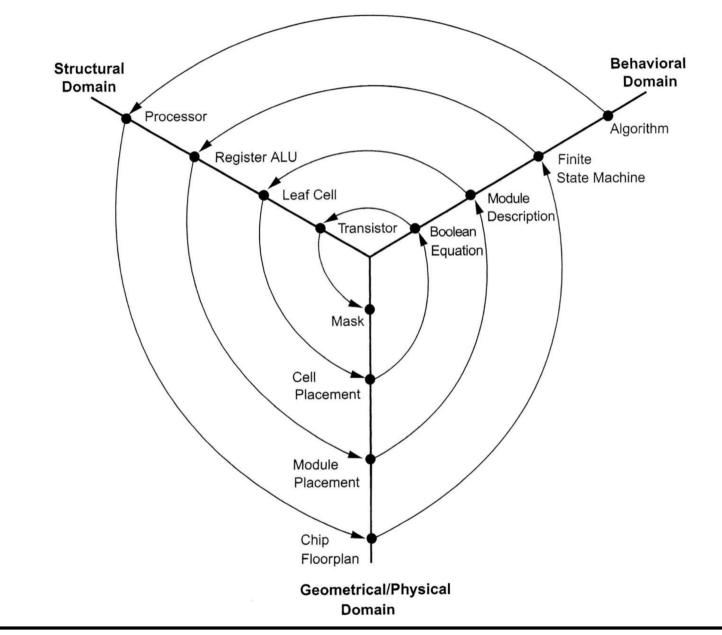
- Just customized place and route
- Ex memory



### **Can CAD Tool Do Everything?**

- Tools are smart and stupid
  - It can't think for you, be aware of the limitations
- Tools do output but do not judge
  - Need to know how to use tool correctly
  - Need to be able to identify the validity
- Tools always update
  - Need to follow the steps
  - Choose the right tool for you
- You can even create new tools
  - Startup opportunity

#### **Y-Chart**



### **Structured Design**

- Hierarchy: Divide and Conquer
  - Recursively divide system into modules
- Regularity
  - Reuse modules wherever possible
- Modularity: well-defined Interfaces
  - Allow modules to be treated as black boxes
- Locality
  - Physical and temporal